

Wet Chemistry Solvent Bench

Operating Procedures [LINK](#)



Equipment Description:

The chemical bench has with two temperature-controlled, explosion-proof hotplates, one ultrasonic tank, one quick dump rinser (QDR) and one sink. The hotplate temperatures are controlled via a closed-loop control system with redundant over-temperature safety interlocks. The bench touch-screen controller allows programming of the ultrasonic timing and QDR functions.

<i>Materials Allowed</i>	<i>Materials Not Allowed</i>
III-V compounds	Acids
1165 Remover	Bases
Acetone	Oxidizers
Glass	
Isopropanol	
Metals	
Methanol	
Photoresists	
Silicon	
Silicon dioxide	
Silicon nitride	
SU-8	